DERWENT-ACC-NO: 1980-72052C
DERWENT-WEEK: 198041

TITLE: Positive photoresist compsn. - comprises halogen substituted alkyl
acrylic! polymers, for prodn. of integrated circuits and optics

INVENTOR: COUTTET, A; DUBOIS, J C ; ERANIAN, A

PATENT-ASSIGNEE: THOMSON CSF[CSFC]

PRIORITY-DATA: 1979FR-0018467 (July 17, 1979) , 1979FR-0006136 (March 9, 1979)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
EP 16679 A	October 1, 1980	F	000	N/A
DE 3060510 G	July 29, 1982	N/A	000	N/A
EP 16679 B	June 9, 1982	F	000	N/A
FR 2451050 A	November 7, 1980	N/A	000	N/A
FR 2461967 A	March 13, 1981	N/A	000	N/A
JP 55133038 A	October 16, 1980	N/A	000	N/A
JP 88007377 B	February 16, 1988	N/A	000	N/A
US 4268590 A	May 19, 1981	N/A	000	N/A

DESIGNATED-STATES: DE GB IT DE GB IT

CITED-DOCUMENTS: DE 2743763; FR 2299665 ; FR 2339184 ; FR 2389156 ; GB 780218
; US 4061829 ; 2.Jnl.Ref

INT-CL (IPC): C08F220/22; G03C001/72 ; G03F001/00 ; G03F007/10

ABSTRACTED-PUB-NO: EP 16679A
BASIC-ABSTRACT: Photomask compsn. decomposing when irradiated comprises
copolymers of the alpha-alkylacrylic series substd. by >=2 halogen atoms and of
formula where the R's are 1-10C alkyl substd. by F, Cl or Br, the indices a,
a', b, b', c and c' being integers and are 0 or positive; m, n and p are 0 or
positive integers, only one of m, n and p being 0.

The compsn. is used as a positive photoresist and is degradable by electrons,
UV (200-300 nm), X-rays (4-50 Angstroms) and gamma-rays. The compsn. exhibits
high resolution and is used for the prodn. of integrated circuits and optics.

TITLE-TERMS:
POSITIVE PHOTORESIST COMPOSITION COMPRISE HALOGEN
SUBSTITUTE ALKYL POLYACRYLIC
POLYMER PRODUCE INTEGRATE CIRCUIT OPTICAL

DERWENT-CLASS: A14 A89 G06 L03 P83 P84 U11

CPI-CODES: A04-E; A10-E05; A10-E10; A12-E07A; A12-L02B;
A12-L02E; A12-L03;
G06-D03; G06-D06; G06-F03C; L03-D03B; L03-H04E2;

EPI-CODES: U11-A09;

POLYMER-MULTIPUNCH-CODES-AND-KEY-SERIALS:
Key Serials: 0036 0208 0209 0210 0212 0502 0503 0516 0517
0530 0531 0537 0538
0544 0545 0551 0552 0558 0559 0565 0566 0572 0573 0579 0580
0593 0594 0600 0601
1995 2009 2016 2023 2027 2066 2116 2122 2123 2194 2198 2201
2318 2393 2427 2440
2507 2598 2602 2729 2740 2743 2805 2851 0228 0229 0505 0519
0547 0603 2177 2179
2184 2185 2189 2206 2207
Multipunch Codes: 011 034 045 051 062 063 064 074 077 079
081 082 083 084 085
092 098 145 231 236 246 264 266 27& 28& 316 33- 332 353 355
359 398 402 41- 414
431 445 477 524 541 623 627 628 649 658 679 681 691 722 726

729 011 03& 03- 045
062 063 064 074 077 079 081 083 085 238 239 241 244 250 343
360 58- 723 724

DERWENT-ACC-NO: 1997-532795
DERWENT-WEEK: 199749

TITLE: Acryloyl:di:methyl:naphthalene compound - is polymerised to give
light-degradable product for use in packaging or as resist for fine processing

PATENT-ASSIGNEE: JAPAN ENERGY CORP[NIHA]

PRIORITY-DATA: 1996JP-0065637 (March 22, 1996)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
JP 09255726 A	September 30, 1997	N/A	016	C08F 016/36

APPLICATION-DATA:

PUB-NO	APPL-DESCRIPTOR	APPL-NO	APPL-DATE
JP09255726A	N/A	1996JP-0065637	March 22, 1996

INT-CL (IPC): B01J027/125; B01J027/135 ; B01J031/02 ; C07B061/00 ;
C07C045/65 ; C07C049/796 ; C08F016/36

ABSTRACTED-PUB-NO: JP09255726A
BASIC-ABSTRACT: An acryloyldimethylnaphthalene compound of formula (I) is new.

Also claimed are (1) a halopropionyldimethylnaphthalene compound of formula
(II) or (III), where X = halogen; (2) polyacryloyldimethylnapht halene having a
repeat unit of formula (IV) which is prepared by polymerising compound (I); and
(3) polyacryloyldimethylnaphthalene-methylm ethacrylate copolymer having a
repeat unit of formula (IV) and (V).

USE - The polymer is suitable as a packaging material or resist for fine

processing.

ADVANTAGE - The (co)polymer is light-degradable and can form pattern with an
electron beam and X-ray or ion beam and has high definition.

CHOSEN-DRAWING: Dwg.0/0

TITLE-TERMS:
ACRYLYL DI METHYL NAPHTHALENE COMPOUND POLYMERISE LIGHT DEGRADE PRODUCT PACKAGE
RESIST FINE PROCESS

DERWENT-CLASS: A14 A89 A92

CPI-CODES: A04-C; A12-L02E; A12-P01;

ENHANCED-POLYMER-INDEXING:
Polymer Index [1.1]
018 ; G0373 G0340 G0339 G0260 G0022 D01 D12 D10 D26 D51 D53 D58
D63 F41 F89 D11 D20 D18 D32 D78 D93 ; H0271 ; L9999 L2471 ; L9999
L2131 ; L9999 L2835 ; K9665
Polymer Index [1.2]
018 ; ND08
Polymer Index [1.3]
018 ; C999 C066 C000 ; C999 C259
Polymer Index [1.4]
018 ; R01677 D00 D70 Al 3A Cl 7A ; C999 C022 C000 ; C999 C259
Polymer Index [2.1]
018 ; G0373 G0340 G0339 G0260 G0022 D01 D12 D10 D26 D51 D53 D58
D63 F41 F89 D11 D20 D18 D32 D78 D93 ; H0000 ; H0282 ; L9999 L2391
; L9999 L2095*R ; M9999 M2095*R ; K9814 K9803 K9790 ; K9803*R K9790
; K9847*R K9790 ; P0088
Polymer Index [2.2]
018 ; G0373 G0340 G0339 G0260 G0022 D01 D12 D10 D26 D51 D53 D58
D63 F41 F89 D11 D20 D18 D32 D78 D93 ; R00479 G0384 G0339 G0260 G0022
D01 D11 D10 D12 D26 D51 D53 D58 D63 D85 F41 F89 ; H0022 H0011 ;
H0282 ; L9999 L2391 ; L9999 L2095*R ; M9999 M2095*R ;

K9814 K9803
K9790 ; K9803*R K9790 ; K9847*R K9790 ; P0088
Polymer Index [2.3]
018 ; ND04 ; ND09 ; B9999 B3098 B3010 K9847 ; B9999
B4386 B4240
; Q9999 Q8684 Q8673 Q8606 ; Q9999 Q8366*R

SECONDARY-ACC-NO:
CPI Secondary Accession Numbers: C1997-170069